



## AMENDMENTS TO THE CLAIMS

1. (Currently Amended) A chemical-amplification positive-working photoresist composition which comprises, as a uniform solution in an organic solvent:

(A) a polyhydroxystyrene-based resinous ingredient of which the hydroxyl groups are partly substituted by acid-dissociable substituent groups capable of being dissociated by interacting with an acid; and

(B) a radiation-sensitive acid-generating compound capable of releasing an acid by irradiation, said acid-generating agent being selected from the group consisting of diazomethane compounds and onium salt compounds of which the anionic counterpart is a C<sub>1</sub>-C<sub>15</sub> halogenoalkylsulfonate anion,

the resinous ingredient as the component (A) being a combination comprising (A1) a first polyhydroxystyrene resin substituted for a part from 30 to 60% of the hydroxyl groups by ~~acid-dissociable substituent~~ tert-butoxycarbonyl groups and (A2) a second ~~polyhydroxystyrene resin~~ polyhydroxystyrene resin substituted for a part from 5 to 20% of the hydroxyl groups by ~~acid-dissociable substituent~~ tert-butoxycarbonyl groups which are the same as in the first ~~polyhydroxystyrene resin~~ polyhydroxystyrene resin (A1), ~~of which the degree of substitution by the substituent groups for a part of the hydroxyl groups in the first polyhydroxystyrene resin (A1) is larger than the degree of substitution in the second polyhydroxystyrene resin (A2)~~ with the proviso that the ratio of the maximum weight-average molecular weight  $Mw_{max}$  to the minimum weight-average molecular weight  $[[MW_{min}]]$   $Mw_{min}$  in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than 1.5, and ~~wherein the overall degree of substitution in the resinous ingredient as the component (A) for a part of the hydroxyl groups by the acid-dissociable substituent groups is in the range from 5 to 60% and the acid-dissociable substituent group is selected from the group consisting of tertiary alkoxycarbonyl groups, tertiary alkyl groups, alkoxyalkyl groups and cyclic ether groups and~~

(C) an amino amine compound.

2 to 5. (Canceled)

**6. (Currently Amended)** The chemical-amplification positive-working photoresist composition as claimed in claim 5 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of the first and second polyhydroxystyrene resins (A1) and (A2) in a weight proportion in the range from 1:9 to 9:1.

**7. (Currently Amended)** The chemical-amplification positive-working photoresist composition as claimed in claim 5 1 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of (A1) a first polyhydroxystyrene resin substituted for from 35 to 60% of the hydroxyl groups by the acid-dissociable substituent groups and (A2) a second polyhydroxystyrene resin substituted for from 5 to 15% of the hydroxyl groups by the acid-dissociable substituent groups.

**8. (Original)** The chemical-amplification positive-working photoresist composition as claimed in claim 7 in which the polyhydroxystyrene-based resinous ingredient as the component (A) is a combination of the first and second polyhydroxystyrene resins (A1) and (A2) in a weight proportion in the range from 4:6 to 1:9.

**9. (Canceled)**

**10. (Original)** The chemical-amplification positive-working photoresist composition as claimed in claim 1 in which the ratio of the maximum weight-average molecular weight  $Mw_{max}$  to the minimum weight-average molecular weight  $Mw_{min}$  in the first and second polyhydroxystyrene resins (A1) and (A2) is smaller than 1.3.